


<b>Search Notes</b>  	<b>Application/Control No.</b>  10710698	<b>Applicant(s)/Patent Under Reexamination</b>  CHEN ET AL.
	<b>Examiner</b>  Kourtney R Salzman	<b>Art Unit</b>  4128

<b>SEARCHED</b>			
<b>Class</b>	<b>Subclass</b>	<b>Date</b>	<b>Examiner</b>
204	192 and 192.12; 298, 298.16	11/29/2007	krs

<b>SEARCH NOTES</b>		
<b>Search Notes</b>	<b>Date</b>	<b>Examiner</b>
Inventor Search in PALM	11/29/2007	krs
Assignee Search in PALM	11/29/2007	krs
Keyword Searching: axial\$3, magnet\$4, rotating, magnetron, method, backplate, degree, symmetr\$3, target in EAST	11/29/2007	krs
Assignee Search for Applied Materials, Inc. patents in EAST	11/29/2007	krs
Updated Searches in EAST	6/23/2008; 12/4/2008	krs
Search PAJ for magnetron sputtering and polarity	6/23/2008	krs

<b>INTERFERENCE SEARCH</b>			
<b>Class</b>	<b>Subclass</b>	<b>Date</b>	<b>Examiner</b>

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